

Notice of References Cited	Application/Control No. 10/663,691	Applicant(s)/Patent Under Reexamination INAO ET AL.	
	Examiner John Ruggles	Art Unit 1756	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,236,033	05-2001	Ebbesen et al.	250/216
	B	US-2002/0196420	12-2002	Naya, Masayuki	355/71
	C	US-6,171,730	01-2001	Kuroda et al.	430/5
	D	US-6,187,482	02-2001	Kuroda et al.	430/5
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Alkaisi, M. M. et al., "Sub-diffraction-limited patterning using evanescent near-field optical lithography", (1999) Applied Physics Letters, Vol. 75, No. 22, Pages 3560-3562
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.